

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

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**Title of
Invention**

Methods for the optimization of substrate etching in a plasma processing system

Application Number : 10/804430
Confirmation Number: 7228
First Named Applicant: Jisoo Kim
Attorney Docket Number: LMRX-P032/P1205
Art Unit: 1765
Examiner: Nadine G Norton
Search string: (6518174).pn



US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
	1	6518174	2003-02-11	Annapragada, et al.			

Signature

Examiner Name	Date